



D. Thin Film Process Technology 분과

2021년 1월 28일(목), 13:00-14:30 / 채널 A

[TA3-D] 2D Materials

좌장: 안지훈 교수 (한양대학교), 이상운 교수 (아주대학교)

<p>TA3-D-1 13:00-13:30</p>	<p>[초청] Two-dimensional Electron Gas at the Interface of Oxide Heterostructure and Its Applications to Memories and Transistors</p> <p>Sang Woon Lee <i>Department of Energy Systems Research and Department of Physics, Ajou University</i></p>
<p>TA3-D-2 13:30-13:45</p>	<p>Enlargement of Two-Dimensional SnS Grains at Low Temperatures via Substrate Surface Modification</p> <p>In-Hwan Baek^{1,2,3}, Ah-Jin Cho¹, Sangtae Kim⁴, Ga Yeon Lee⁵, Jeong Hwan Han⁶, Taek-Mo Chung⁵, Cheol Seong Hwang^{2,3}, and Seong Keun Kim¹ <i>¹Electronic materials Research Center, KIST, ²Department of Materials Science and Engineering, Seoul National University, ³Inter-University Semiconductor Research Center, Seoul National University, ⁴Department of Nuclear Engineering, Hanyang University, ⁵Division of Advanced Materials, KRICT, ⁶Department of Materials Science and Engineering, Seoul National University of Science and Technology</i></p>
<p>TA3-D-3 13:45-14:00</p>	<p>Low Temperature Growth of Wafer-scale 2D MoS₂ Thin Films by Pulsed Metal-organic Chemical Vapor Deposition</p> <p>Jeong-Hun Choi, Min-Ji Ha, and Ji-Hoon Ahn <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>TA3-D-4 14:00-14:15</p>	<p>Flexible P-channel SnO Thin Film Transistor Fabricated by Low Temperature Atomic Layer Deposition and Intense Pulsed Light Annealing</p> <p>Jina Kim¹, Myeong Gil Chae¹, Jun Choi², Kwan Hyun Cho³, Woongkyu Lee⁴, and Jeong Hwan Han¹ <i>¹Department of Materials Science and Engineering, Seoul National University of Science and Technology, ²Human Convergence Technology Group, KITECH, ³Micro/Nano Scale Manufacturing R&D Group, KITECH, ⁴Department of Electrical Engineering, Myongji University</i></p>
<p>TA3-D-5 14:15-14:30</p>	<p>Three-Dimensional Multi-Stacked Field-Effect Transistor Using Improved Two-Dimensional Electron Gas at the Interface of Al₂O₃/ZnO Ultra-Thin Film Heterostructures</p> <p>Ji Hyeon Choi¹, Tae Jun Seok¹, Jae Hyun Yoon¹, Yuhang Liu¹, Sang Woon Lee², and Tae Joo Park¹ <i>¹Department of Materials Science and Chemical Engineering, Hanyang University, ²Department of Energy Systems Research and Department of Physics, Ajou University</i></p>